

**Notice of References Cited**

Application/Control No.

10/783,979

Applicant(s)/Patent Under  
Reexamination  
ASUKE ET AL.

Examiner

JASON L. LAZORCIK

Art Unit

1791

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**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,261,378	07-2001	Hashimoto et al.	134/6
	B	US-			
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	D	US-			
	E	US-			
	F	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	WO 9003597 A1	04-1990	World Intellect	JOHN et al.	
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	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Photoresist Processing ( <a href="http://web.archive.org/web/20060714103026/http://www.siliconfareast.com/resist-processing.htm">http://web.archive.org/web/20060714103026/http://www.siliconfareast.com/resist-processing.htm</a> ) Accessed 9/15/2008 - General teaching showing annealing or soft bake of photoresist is conventional in the art
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.